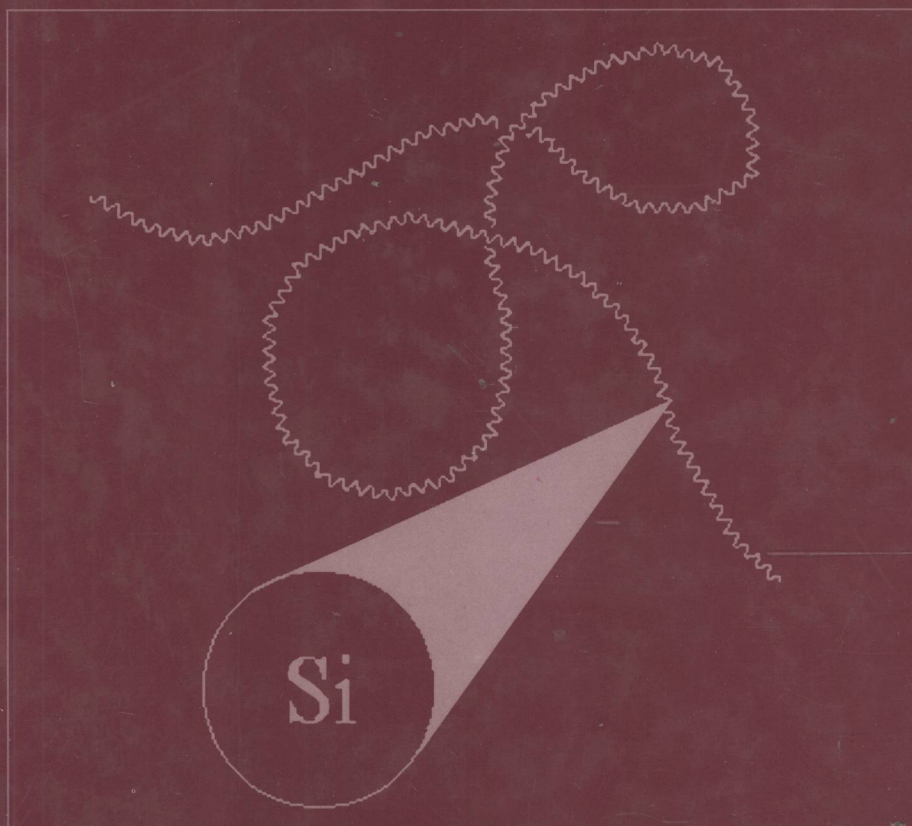


Silicon-Containing Polymers

The Science and Technology of
Their Synthesis and Applications

Richard G. Jones, Wataru Ando and
Julian Chojnowski (Eds.)



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Silicon-Containing Polymers

The Science and Technology of Their Synthesis
and Applications

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PREFACE

BACKGROUND

Polysiloxanes have chains constructed of alternately arranged silicon and oxygen atoms with organic groups attached to the silicon atoms. This structure gives them a unique combination of properties that hold great interest for a host of practical applications. Although they have been known and manufactured for many years, their applications continue to expand rapidly and this boosts progress in the generation of new and modified polysiloxanes.

Polysiloxanes constitute the oldest known class of silicon-based polymers and the broadest one when viewed in terms of the variety of structures differing in topology and the constitution of organic substituents. There are also many and various types of siloxane copolymers, some of purely siloxane structure and others of siloxane-organic composition. There is no doubt that polysiloxanes are the most technologically important silicon-based polymers. The broad class of model materials known as silicones is based on polysiloxanes. They are also the best known, as most research in the area of silicon polymers has for many years been directed towards the synthesis of new polysiloxanes, to understanding their properties and to extending their applications.

It is, thus, obvious that polysiloxanes could not be missing from any book on silicon-based polymers. However, since the concept of the present monograph was to include all silicon polymer types in one melting pot it was decided that considerable attention should also be paid to the relatively new classes: polycarbosilanes, polysilazanes and polysilanes. To date, although they hold the interest of many silicon chemists, there has been relatively little review literature devoted to these polymers. They are nonetheless the subjects of a great number of scientific papers and considered to be materials of the future. In this latter context it was recognised that there are a number of topics of current importance, either from a technological point of view or because they relate closely to broader initiatives in polymer science, and these have also been singled out for particular consideration.

SCOPE

The concept of the book as presented above has confined polysiloxanes to fewer chapters than they might be perceived to deserve from their importance. However, taking account of the extensive review literature that is already available, the subjects selected for inclusion in the section devoted to polysiloxanes address important current trends in siloxane polymer science and technology. Thus, there is coverage of the modification of polysiloxane side groups to give the polymers new reactivity or new physical properties. The content on block copolymers and copolymer networks is directed to meeting the considerable interest of chemists and technologists in new siloxane-organic hybrids. Interest in polysiloxane networks is related to two important and still developing classes of silicone materials: silicone rubbers and silicone resins.

This is reflected in chapters devoted to silicone elastomers and to silsesquioxanes respectively. Among the important features of polysiloxanes that determine their wide-ranging applications are their unusual surface and thermal properties, so current developments in these areas have been included. Some important aspects of polysiloxanes are held over for consideration later in the book under special topics, but at the end of this section a perspective on future developments in polysiloxane science and technology is presented.

Polycarbosilanes and polysilazanes are covered in a special section. Because of their importance as preceramic materials, both established and potential, they have a technological significance second only to the polysiloxanes. The polysilazanes have nitrogen rather than carbon as the chain heteroatom and, in contrast to the polycarbosilanes, are relatively new materials. The editors believe that the two chapters of this special section lend the correct emphasis to these topics.

The next section is devoted to polysilanes and related polymers. The main difference between a polysilane and a polymer with a saturated carbon backbone is that there is significant electronic delocalisation within the σ -bonded framework of the former that, as a consequence of the smaller dimensions of the carbon atom, is not possible in the latter. This single feature plays a dominant role in determining the spectroscopic, electroactive, thermal and mechanical properties of polysilanes. The polysilylarylenes and polysilylalkylenes often share such properties. It is for this reason that this section groups all such polymers together in presentations of the current thinking surrounding their syntheses, and structural and property characterisations. A reliable strategy for the synthesis of polysilanes from accessible starting materials is still an unrealised objective. Accordingly, the different approaches to their synthesis and modification are covered. The characteristic spectroscopic, electronic and electrical properties of polysilanes are dealt with in two chapters, the thermal properties in another, and there are others that give appropriate consideration to the wealth of silicon chemistry directed to the synthesis of new silicon-backbone and main chain substituted polymer variants.

The challenge presented by silicon-based polymers is all the more intriguing because of the rapid growth over the past decade in the number of structural types available and our increasing understanding of the special and highly flexible role that silicon plays in these materials. The final section of this text explores such special topics. For instance, sol-gel technology has become a popular way to create organic/inorganic hybrid materials and nanocomposites. The silica-like structures formed around surfactant micelles afford solids of highly regular and controlled porosity. In recent years, the development of methods for the directed synthesis of macromolecules with precisely defined structures has also generated considerable excitement in the polymer science community, and one of the most widely studied is the class of hyperbranched polymers known as dendrimers. Organosilicon chemistry offers a number of high yield, selective reactions that are suitable for dendrimer construction. Chiral control is another such current area of chemical endeavour and optically active silicon-containing polymers are just beginning to be studied. Millennium old silicate ceramics have now been supplemented by the new ceramic materials derived from pyrolysis of formable preceramics polymers based on silicon. Progress has been made in the conversion of organofunctional silicon sol-gels and silicone resins to silicon oxycarbide ceramics. Polymeric materials have found widespread use in the electronics

industry both in the manufacturing processes used to generate today's microcircuitry and in other component structures of complete devices. The importance of polymers in such applications arises from our ability to design and synthesise versatile materials with the precise functionalities and process properties required. To a large degree, the progress enjoyed by the device industries has relied on parallel advances in polymeric materials technologies. Amongst silicon polymers, polysilanes have played a notable role as lithographic imaging materials and as dielectric, effective luminescence and large carrier mobility materials.

As a consequence of the overlap of the subject matter of different contributors, some repetition has proved to be unavoidable. In addition, we realise that this monograph does not cover what others may deem to be important aspects of silicon-based polymer science and technology. In the light of our present experience, and given the benefit of hindsight, we hope that the subjects that might be viewed as serious omissions can be included in subsequent editions of the book.

Wataru Ando, Julian Chojnowski and Dick Jones

Wataru Ando received his Ph.D. degree from Osaka City University in 1963. This was followed by post-doctoral research at the University of California, Los Angeles with Professor C. S. Foote and then at Princeton with Professor Maitland Jones Jr. On his return to Japan in 1967 he was appointed an associate professor at Gunma University and in 1975 to a full professorship at the University of Tsukuba. He is now an Emeritus Professor of the University of Tsukuba and since 1998 a consultant of Dow Corning. He received the DAAD Fellowship in 1987, Alexander Humboldt-Forschungscprise in 1992, the Chemical Society of Japan Award in 1994, the American Chemical Society Kipping Award in 1996, and a Purple Ribbon Medal in 1997. His research interests embrace high-energy molecules, and especially synthesis and reactive intermediates in carbon, organosilicon, organogermanium and heteroatom chemistry.

Julian Chojnowski graduated from Lodz Technical University, Poland, from where in 1963 he also received his Ph.D. degree after researching under the supervision of Professor Stanislaw Chrzczonowicz. His post-doctoral research was carried out at the University of Wisconsin-Milwaukee, USA, with Professor Werner W. Brandt. He achieved his habilitation in 1971. Since 1972 he has been a research group leader at the Centre of Molecular and Molecular Studies of the Polish Academy of Sciences at Lodz in Poland where he was nominated Professor in 1983. He has been a visiting professor at the Universities Montpellier II and Paris XIII in France, and consultant to Dow Corning. His research interests have focussed on reaction mechanisms in silicon chemistry and silicon polymer formation.

Dick Jones graduated from Victoria University of Wellington in New Zealand before studying for his Ph.D. degree under the direction of the late Professor Lord Dainton FRS at the University of Leeds in Britain. His first appointment, in 1966, was to a Lectureship in Applied Chemistry at the former Lanchester Polytechnic in Coventry. In 1970 he moved to a lectureship at the University of Kent at Canterbury where he is now

Professor of Polymer Science and presently the Head of the School of Physical Sciences. In 1980 he was a visiting professor at the University of Southern California. His research interests include mechanisms of polymerisation and the synthesis, modification and characterisation of polymers for application as microlithographic resists, and in recent years polysilanes have held a particular fascination.

ACKNOWLEDGEMENTS

Underpinning the culture of science is the notion of open collaboration in the pursuit of understanding, and it knows no national boundaries. This book is an excellent example of the fruit born from such collaboration. It could not have been brought to print without the patience and forbearance of the many contributors from different countries as my co-editors and I have painstakingly sought a balanced structure and as consistent a style as is possible. We sincerely thank them.

I should also like to thank my co-editors who, from the day in Montpellier in 1996 when we first agreed to pursue this task, have maintained close contact with me and sought to resolve the many problems that we have met along the way.

The full text was eventually assembled in Canterbury, UK, where the overall editing was carried out. I was ably assisted in this task by one of my research students, Alkay Mustafa, who I thank for undertaking a substantial amount of the standardisation of the layout in readiness for camera-ready formatting. I also thank my colleague, 'JJ' James, for his skill in drawing diagrams. It still took many weekends and a lot of the time that I would otherwise have shared with the people around me. It is impossible to measure the support that I got from the person closest to me and any expression of appreciation seems almost inadequate when compared to the sacrifice but my gratitude could not be tendered with more sincerity.

Dick Jones



*Photograph of the Editors taken in May 1999 during the 12th International Symposium of Organosilicon Chemistry, Sendai, Japan
(from left to right: Wataru Ando, Richard G. Jones, Julian Chojnowski).*

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